

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	659	((semiconductor or substrate or wafer) near5 (water or liquid or solution or solvent or stripper)) and ((semiconductor or substrate or wafer) near5 (back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior)) and ((back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior) near5 (seal\$4 or gasket or meniscus or barrier or guard or deflector or baffle or shield or rib)) and ((workpiece or semiconductor or substrate or wafer) near5 (chuck or spindle or rotat\$4 or rotary or spin\$4 or centrifug\$4))	US-PGPU B; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/02/08 06:51
L3	789	((workpiece or semiconductor or substrate or wafer) near5 (washing or clean\$4 or decontaminat\$4 or rins\$4 or strip\$4 or develop\$4)) and ((workpiece or semiconductor or substrate or wafer) near2 (back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior)) and ((back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior) near2 (seal\$4 or gasket or meniscus or defelector or baffle or shield))	US-PGPU B; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/02/08 06:50

EAST Search History

Jns

L7	224	((workpiece or semiconductor or substrate or wafer) near5 (water or liquid or solution or solvent or stripper or developer or chemical or surfactant or formulation or fluid)) and ((workpiece or semiconductor or substrate or wafer) near5 (rearside or back or baskside or rear or bottom or underneath or rearward\$4 or reverse or posterior)) and ((rearside or back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior) near8 (seal\$4 or gasket or meniscus or barrier or guard or deflector or baffle or shield or rib) near8 (water or liquid or solution or solvent or stripper or developer or chemical or surfactant or formulation or fluid)) and ((workpiece or semiconductor or substrate or wafer) near5 (chuck or spindle or rotat\$4 or rotary or spin\$4 or centrifug\$4))	US-PGPU B; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/02/08 09:06
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EAST Search History

7th

S3	141	((workpiece or semiconductor or substrate or wafer) near5 (washing or clean\$4 or decontaminat\$4 or rins\$4 or strip\$4 or develop\$4)) and ((workpiece or semiconductor or substrate or wafer) near5 (back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior)) and ((back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior) near8 (ring or circle or hook or loop or band) near8 (seal\$4 or gasket or meniscus or barrier))	US-PGPU B; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/02/07 11:46
S8	192	((workpiece or semiconductor or substrate or wafer) near5 (washing or clean\$4 or decontaminat\$4 or rins\$4 or strip\$4 or develop\$4)) and ((workpiece or semiconductor or substrate or wafer) near5 (back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior)) and ((back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior) near8 (ring or circle or hook or loop or band) near8 (seal\$4 or gasket or meniscus or barrier or guard or defelector or baffle or shield))	US-PGPU B; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/02/07 13:18

EAST Search History

WLS

S13	788	((workpiece or semiconductor or substrate or wafer) near5 (washing or clean\$4 or decontaminat\$4 or rins\$4 or strip\$4 or develop\$4)) and ((workpiece or semiconductor or substrate or wafer) near2 (back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior)) and ((back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior) near2 (seal\$4 or gasket or meniscus or barrier or guard or defelector or baffle or shield))	US-PGPU B; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/02/07 13:22
S17	710	((workpiece or semiconductor or substrate or wafer) near5 (washing or clean\$4 or decontaminat\$4 or rins\$4 or strip\$4 or develop\$4)) and ((workpiece or semiconductor or substrate or wafer) near5 (back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior)) and ((back or baskside or rear or botton or underneath or rearward\$4 or reverse or posterior) near5 (seal\$4 or gasket or meniscus or barrier or guard or deflector or baffle or shield or rib)) and ((workpiece or semiconductor or substrate or wafer) near5 (chuck or spindle or rotat\$4 or rotary or spin\$4 or centrifug\$4))	US-PGPU B; USPAT; USOCR; EPO; JPO; DERWEN T; IBM_TDB	OR	ON	2007/02/08 06:40